

Electronic Acknowledgement Receipt

EFS ID:	1109351
Application Number:	10693202
Confirmation Number:	2334
Title of Invention:	Method for dual damascene patterning with single exposure using tri-tone phase shift mask
First Named Inventor:	Sia Kim Tan
Customer Number:	30402
Filer:	William John Stoffel
Filer Authorized By:	
Attorney Docket Number:	CS02-099
Receipt Date:	11-JUL-2006
Filing Date:	24-OCT-2003
Time Stamp:	19:01:57
Application Type:	Utility
International Application Number:	

Payment information:

Submitted with Payment	no
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File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part	Pages
1	Amendment After Final	cs02-099-roa2-final-dated-2006-05-17-ef-uspto.pdf	284531	no	27

Warnings:	
Information:	
Total Files Size (in bytes):	284531
<p>This Acknowledgement Receipt evidences receipt on the noted date by the USPTO of the indicated documents, characterized by the applicant, and including page counts, where applicable. It serves as evidence of receipt similar to a Post Card, as described in MPEP 503.</p> <p><u>New Applications Under 35 U.S.C. 111</u> If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.</p> <p><u>National Stage of an International Application under 35 U.S.C. 371</u> If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.</p>	